

<b>Notice of References Cited</b>	Application/Control No. 10/760,661	Applicant(s)/Patent Under Reexamination JONES ET AL.	
	Examiner Bobby Ramdhanie, Ph.D.	Art Unit 1709	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,194,326	02-2001	Gilton, Terry L.	438/745
*	B	US-6,544,338	04-2003	Batchelder et al.	118/641
*	C	US-2002/0101576	08-2002	Shabani et al.	356/36
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	SEMI-Standard M33-0998 (1998). Available online.
	V	Shabani, M.B.; Yoshimi, T.; Abe, H." Low-Temperature Out Diffusion of Cu from Silicon Wafers." J. Electrochem. Soc. 1996. 143, 6, pages 2025-2029.
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.